

Variable	Mean	SD	Min	Max	Skewness	Kurtosis	Normality
Age	35.5	10.5	20	65	0.1	3.0	0.95
Gender	0.5	0.5	0	1	0.0	3.0	0.95
Education	12.5	1.5	9	16	0.2	3.2	0.95
Income	1500	500	500	3000	0.5	3.5	0.95
Marital Status	0.7	0.5	0	1	0.0	3.0	0.95
Occupation	1.5	1.0	1	5	0.3	3.3	0.95
Health Status	0.8	0.4	0	1	0.0	3.0	0.95
Stress Level	2.5	1.5	1	5	0.4	3.4	0.95
Life Satisfaction	3.5	1.0	1	5	0.2	3.2	0.95
Resilience	2.0	1.0	1	5	0.3	3.3	0.95
Emotional Stability	3.0	1.0	1	5	0.2	3.2	0.95
Physical Health	4.0	1.0	1	5	0.1	3.1	0.95
Mental Health	3.0	1.0	1	5	0.2	3.2	0.95
Social Support	2.5	1.0	1	5	0.3	3.3	0.95
Life Events	1.5	1.0	1	5	0.4	3.4	0.95
Personal Growth	3.0	1.0	1	5	0.2	3.2	0.95
Relationship Quality	2.0	1.0	1	5	0.3	3.3	0.95
Work-Life Balance	2.5	1.0	1	5	0.4	3.4	0.95
Financial Stability	3.5	1.0	1	5	0.2	3.2	0.95
Healthcare Access	4.0	1.0	1	5	0.1	3.1	0.95
Community Involvement	2.0	1.0	1	5	0.3	3.3	0.95
Personal Resilience	3.0	1.0	1	5	0.2	3.2	0.95
Emotional Well-being	3.5	1.0	1	5	0.1	3.1	0.95
Physical Well-being	4.0	1.0	1	5	0.0	3.0	0.95
Social Well-being	3.0	1.0	1	5	0.2	3.2	0.95
Life Satisfaction	3.5	1.0	1	5	0.1	3.1	0.95
Resilience	2.0	1.0	1	5	0.3	3.3	0.95
Emotional Stability	3.0	1.0	1	5	0.2	3.2	0.95
Physical Health	4.0	1.0	1	5	0.1	3.1	0.95
Mental Health	3.0	1.0	1	5	0.2	3.2	0.95
Social Support	2.5	1.0	1	5	0.3	3.3	0.95
Life Events	1.5	1.0	1	5	0.4	3.4	0.95
Personal Growth	3.0	1.0	1	5	0.2	3.2	0.95
Relationship Quality	2.0	1.0	1	5	0.3	3.3	0.95
Work-Life Balance	2.5	1.0	1	5	0.4	3.4	0.95
Financial Stability	3.5	1.0	1	5	0.2	3.2	0.95
Healthcare Access	4.0	1.0	1	5	0.1	3.1	0.95
Community Involvement	2.0	1.0	1	5	0.3	3.3	0.95
Personal Resilience	3.0	1.0	1	5	0.2	3.2	0.95
Emotional Well-being	3.5	1.0	1	5	0.1	3.1	0.95
Physical Well-being	4.0	1.0	1	5	0.0	3.0	0.95
Social Well-being	3.0	1.0	1	5	0.2	3.2	0.95

5

Such use of a basic material can significantly decrease or even completely eliminate notching of an overcoated photoresist relief image. Antireflective formulations of the invention are preferably crosslinking compositions and may contain a resin component in addition to the basic additive. Antireflective compositions of the invention can be effectively used at a variety of wavelengths used to expose an overcoated photoresist layer, including 248 nm and 193 nm.